

XJP-607



XJP-607 Industrial Metallurgical microscope is developed and aimed at the semiconductor industry, wafer manufacturing, electronic information industry, metallurgical industry. Used as an advanced Metallurgical microscope, the user can experience its superb performance when using it. It can be widely used to identify and analyze Semiconductor, FPD, Circuit encapsulation, the circuit substrate, Material, Casting/Metal/Ceramic parts, Precision molds and observe thicker specimen. High quality and reliable optical system bring much clearer and contrast image. The design meets the ergonomics needs and makes you feel comfortable and relaxed in doing your job.

Specification	
Viewing Head	Compensation Free Trinocular Head, Inclined 30° (50mm-75mm)
Eyepiece	WF10×/25mm
	WF10×/20mm,crosshair with reticule 0.1mm
Objective	Long working distance bright and dark field Infinite Plan objectives: 5×/0.1B.D/W.D.29.4mm 10×/0.25B.D/W.D.16mm 20×/0.40B.D/W.D.10.6mm 40×/0.60B.D/W.D.5.4mm
Nosepiece	Quintuple Nosepiece with DIC Jack
Stage	Double layer mechanical stage
	Stage Size: 190mm×140mm
	Moving Range:50mm×40mm
Filter	Flashboard type filters(green,blue,neutral)
Focusing	Coaxial coarse & fine focusing adjustment With rack and pinion mechanism Fine focusing scale value 0.002mm
Light Source	With aperture iris diaphragm and field iris diaphragm, Halogen Bulb 12V/50W, AC85V-230 Brightness Adjustable
Polarizing Device	Analyzer rotatable 360°,Polarizer & Analyzer can be moved in/out of the optical path
Checking Tool	0.01mm Micrometer
Optional Accessory	Two-dimensional measurement software
	Professional metallurgical image analysis software
	Halogen Bulb 12V/100W
	Micrometer eyepiece
	1.3Mega、 2.0 Mega、 3.0 Mega、 5.0 Megapixels CMOS Digital camera eyepieces
	Long working distance bright & dark field Infinite Plan objectives: 50×/0.55B.D/W.D.5.1mm、 80×/0.75B.D/W.D.4mm、 100×/0.80B.D/W.D.3mm
	Precision Stage: X-Y moving range 25mm×25mm, Moving Precision < 5um, Digital handwheel Min.Value:0.1um,360°Rotatable disc
	Photography attachment and CCD Adapter 0.5×、 0.57×、 0.75×
	DIC (10×、 20×、 40×、 100×)

	Planishing tool	
	CCD Camera,colour 1/3"High resolution 520 TV lines	

Characteristics and description

1. Adopt US High-1. UIS infinite-optical system.
2. Adopt long-life halogen light source with much higher light efficiency.
3. Bright and dark field, Polarization and differential interference function.
4. The aspherical Kohler illumination, increasing the brightness of observation.
5. WF10 × (Φ25) Super wide viewing field Eyepiece, long working distance the metallurgical objective with bright and dark field
6. The Quintuple Nosepiece can be equipped with detachable DIC differential interference device.

DIC: Nomarski differential interference contrast observation is deemed to the essential means to check out the materials, semiconductor and metal structure now.